

Amendments to the Drawings:

The attached replacement drawing sheets make changes to Figs. 1-3 and replace the original drawing sheets showing Figs. 1-3.

Attachment: Replacement Drawing Sheets

REMARKS

Claims 12-14 are pending in this application. By this Amendment, claims 12 and 13 are amended and claims 1-4 and 7-9 are canceled.

The Office Action requests that Figs. 1-3 be designated as prior art. By this Amendment, Figs. 1-3 have been amended to recite "prior art."

The Office Action objects to the specification under 37 C.F.R. §1.75(d)(1) and MPEP §608.01(o) for not providing adequate antecedent basis for "follow focus system." By this Amendment, "follow focus system" in claim 12, is amended to "dynamic auto focus system." This is in agreement with the terms used in the specification such as, for example, in paragraphs [0029] and [0030]. Thus, Applicants respectfully request withdrawal of the objection.

The Office Action objects to claim 12 for containing various informalities. By this Amendment, claim 12 has been amended as follows: in line 7, "of" is changed to "on" and "an" is added; in line 14, "silicone" is changed to "silicon"; and in line 19, "crystallized" has been added. Thus, Applicants respectfully request withdrawal of the objection.

The Office Action rejects claims 12-14 under 35 U.S.C. §112, first paragraph, for failing to comply with the written description requirement. Again, the Office Action asserts a lack of support for "follow focus system." As discussed above, by this Amendment, "follow focus system" is amended to "dynamic auto focus system" which has support at, for example, paragraphs [0029] and [0030].

The Office Action further alleges that there is no support for the feature of holographic lithography and a follow focus system. Applicants disagree. Support for this feature is found, for example, in paragraph [0030] which states "in the patterning processes of the polycrystalline silicon layer 41 and the first metal layer 42, holographic lithography and a

dynamic auto focus system are used." Thus, Applicants respectfully request withdrawal of the rejection.

The Office Action rejects claim 13 under 35 U.S.C. §112, second paragraph, as indefinite. By this Amendment, claim 13 is amended to specifically recite "patterning of the crystallized amorphous silicon layer and the gate metal." Thus, Applicants respectfully request withdrawal of the rejection.

In view of the foregoing, it is respectfully submitted that this application is in condition for allowance. Favorable reconsideration and prompt allowance of claims 12-14 are earnestly solicited.

Should the Examiner believe that anything further would be desirable in order to place this application in even better condition for allowance, the Examiner is invited to contact the undersigned at the telephone number set forth below.

Respectfully submitted,


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